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(12) **United States Design Patent**  
**Chen**

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- (54) **MASK**
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- (\*\*) Term: **15 Years**
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- (51) **LOC (13) Cl.** ..... **29-02**
- (52) **U.S. Cl.**  
USPC ..... **D29/108**
- (58) **Field of Classification Search**  
USPC ..... D2/870, 872, 878; D29/100, 102, 103, 104, 105, 106, 107, 108, 110, 122  
CPC .. A41D 13/11; A42B 3/04; A42B 3/18; A42B 3/20; A42B 3/185; A42B 3/226; A42B 3/0406; A61F 9/06; A61F 9/029; A63B 2071/105; A63B 71/08; A63B 71/10  
See application file for complete search history.

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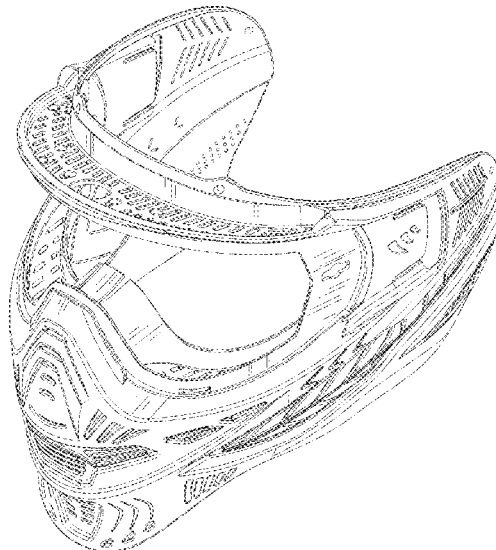
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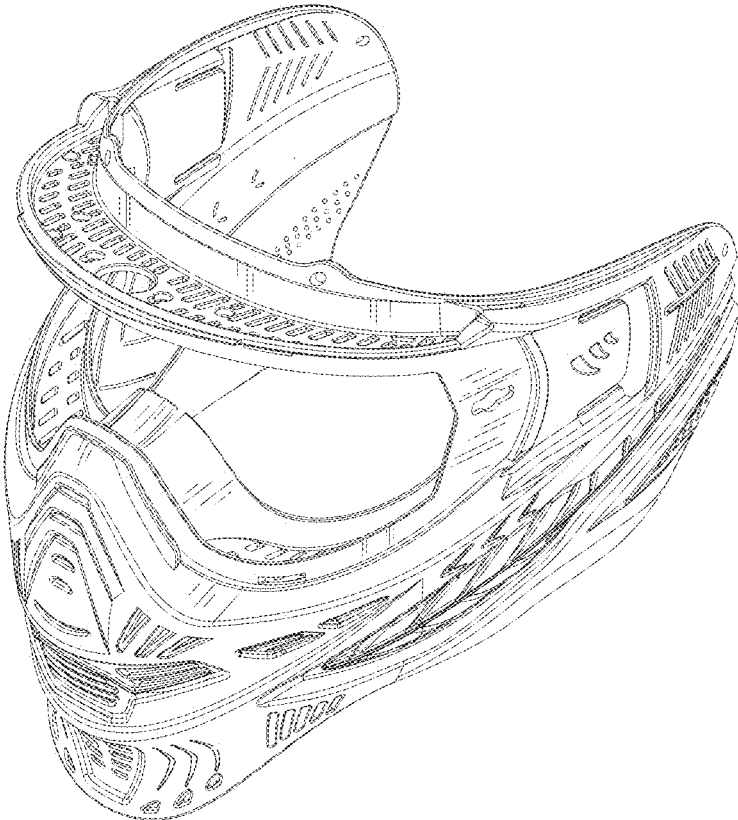
(57) **CLAIM**  
 The ornamental design for a mask, as shown and described.

**DESCRIPTION**

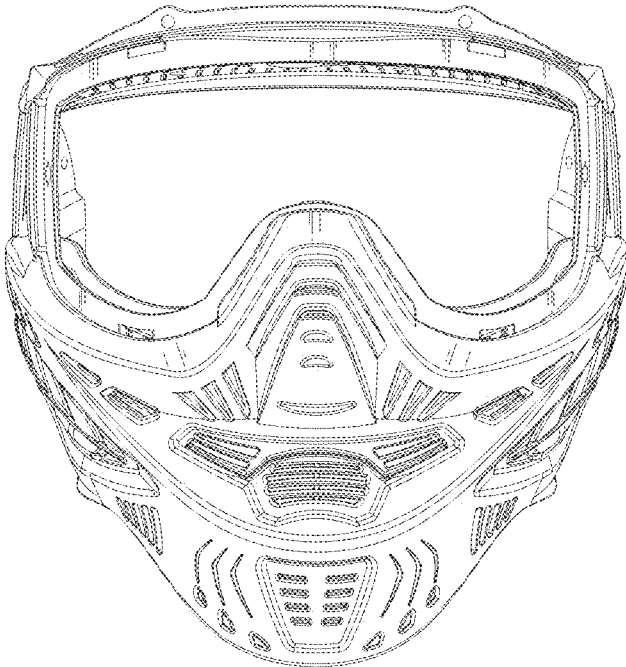
FIG. 1 is a perspective view of a mask showing my design.  
 FIG. 2 is a front elevational view thereof.  
 FIG. 3 is a rear elevational view thereof.  
 FIG. 4 is a left side elevational view thereof.  
 FIG. 5 is a right side elevational view thereof.  
 FIG. 6 is a top plan view thereof; and,  
 FIG. 7 is a bottom plan view thereof.

**1 Claim, 7 Drawing Sheets**

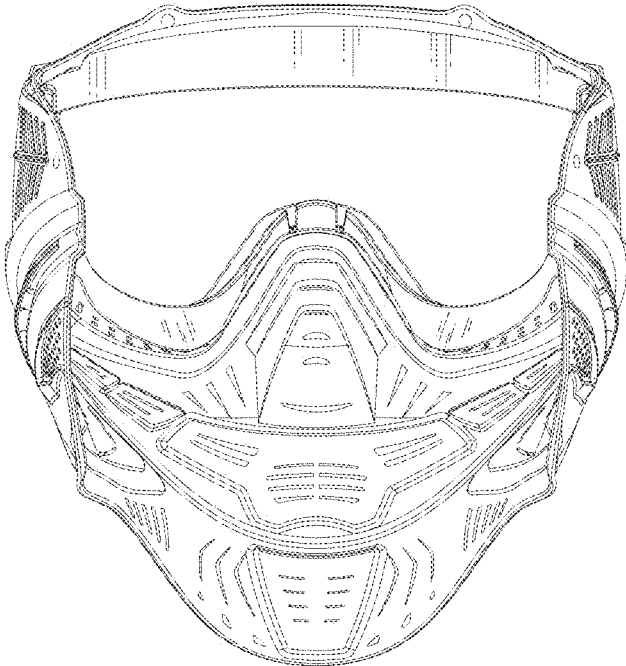




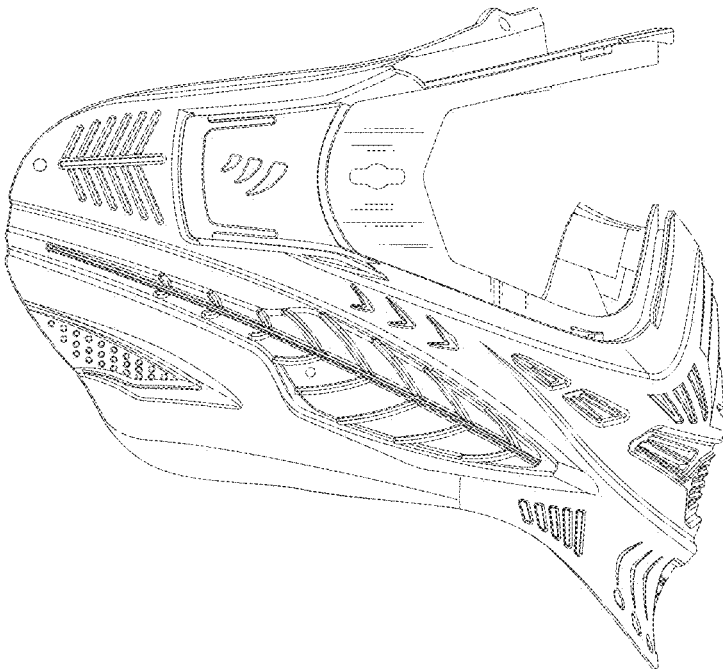
**FIG. 1**



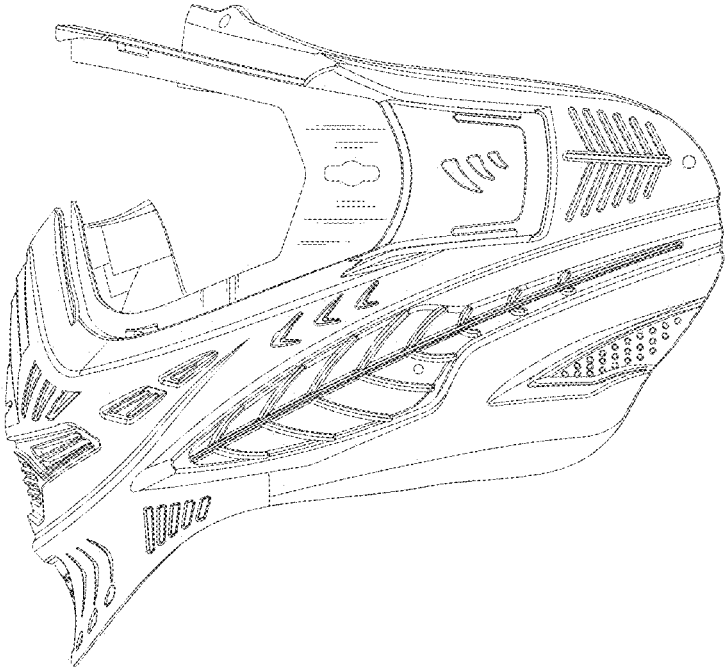
**FIG. 2**



**FIG. 3**



**FIG. 4**



**FIG. 5**



**FIG. 6**



**FIG. 7**